

CLAIM AMENDMENTS

Claims 1-13 (Canceled).

14. (Currently Amended) A substrate treatment ~~assembly apparatus~~ comprising:
a substrate heating device for maintaining a substrate at a temperature higher than
room temperature;
a wetting device for ~~obtaining~~ producing a wet ozone-containing gas by wetting an
ozone-containing gas with a treatment solution;
a supply device for supplying ~~said the~~ wet ozone-containing gas from the wetting
device to a work object on a surface of ~~said the~~ substrate, said supply device comprising a
gas disperser including a plurality of apertures aligned in a plurality of rows in a width
direction of the work object, the apertures in adjacent rows not being aligned with each other
in a direction perpendicular to the rows, and at least one of said gas disperser and the
substrate being movable in a direction perpendicular to the rows;
a gas conduit connecting said wetting device to said supply device; and
a wet ozone-containing gas heating device for heating ~~said the~~ wet ozone-containing
gas ~~so as to be at a temperature approximately at least equal to or greater than~~ the
temperature of ~~said the~~ substrate.

Claim 15 (Canceled).

16. (Currently Amended) The substrate treatment assembly according to Claim 15
wherein spacing between adjacent rows of ~~aperture~~ apertures in said gas disperser is at least
5 mm or more.

17. (Currently Amended) A substrate treatment ~~assembly apparatus~~ for supplying
an ozone-containing gas and a treatment solution to a work object on a surface of a substrate
~~through, the assembly including~~ a treatment agent supply plate ~~disposed~~ facing ~~said the~~ work
object and ~~through which the treatment solution is supplied, in which spacing between~~
wherein a surface of ~~said the~~ work object ~~and is spaced from~~ said treatment agent supply
plate ~~is~~ by a distance in a range between 0.1 mm and 1.0 mm.